Form PTO 1449 U.S. DEPAR MENT OF COMMERCE ATTY DOCKET NO.
(Modified) PATENT AND RADEMARK OF ICE
211147US99

SERIAL NO. 09/903,784

OT OF DE				APPLICANT		JU9/903,762	
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				FILING DATE JULY 13, 2001		GROUP 2826	
				U.S. PATENT DOCUMENTS			
XAMINER INITIAL	<u> </u>	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIAT
FE	AA	3,802,967	04/09/74	Ladany et al.		3	" TU THOTTIAL
	АВ	4,174,422	11/13/79	Matthews et al.	·		
	AC	4,404,265	09/13/83	Manasevit		 	
	AD	4,482,906	11/13/84	Hovel et al.			
	AE	4,523,211	06/11/85	Morimoto et al.		 	
	AF	4,661,176	04/28/87	Manasevit			
	AG	4,793,872	12/27/88	Meunier et al.			
	АН	4,846,926	07/11/89	Kay et al.			
	AJ	4,855,249	08/08/89	Akasaki et al.			
	ΑI	4,891,091	01/02/90	Shastry			
	AK	4,912,087	03/27/90	Aslam et al.			
	AL	4,928,154	05/22/90	Umeno et al.			
	АМ	4,963,949	10/16/90	Wanlass et al.			
	AN	5,141,894	08/25/92	Bisaro et al.			
	AO	5,159,413	10/27/92	Calviello et al.			
	AP	5,173,474	12/22/92	Connell et al.			
	AQ	5,221,367	06/22/93	Chisholm et al.			
	AR	5,225,031	07/06/93	McKee et al.			
	AS	5,358,925	10/25/94	Neville Connell et al.			
1	ΑT	5,393,352	02/28/95	Summerfelt			
1 1	ΑU	5,418,216	05/23/95	Fork			
1	٩V	5,450,812	09/19/95	McKee et al.			
1	w	5,478,653	12/26/95	Guenzer			
β	X	5,482,003	01/09/96	McKee et al.			
Ā	Υ	5,514,484	05/07/96	Nashimoto			
<u> </u>	Z	5,556,463	09/17/96	Guenzer			
В	BA	5,588,995	12/31/96	Sheldon			
В	В	5,670,798	09/23/97	Schetzina	- 		
В	C	5,733,641	03/31/98	Fork et al.			
В	D	5,735,949	04/07/98	Mantl et al.			
В	E	5,741,724	04/21/98	Ramdani et al.			
В	F	5,810,923	09/22/98	Yano et al.			
В	G	5,830,270	11/03/98	McKee et al.			
В	Н	5,912,068	06/15/99	Jia			
Ві	1	6,020,222	02/01/00	Wollesen	- - 		
В	J	6,045,626	04/04/00	Yano et al.	- -		
Bi	ĸ	6,064,078	05/16/00	Northrup et al.		-	
BI	-	6,064,092	05/16/00	Park			
В	И	6,096,584	08/01/00	Ellis-Monaghan et al.			
Br	V	6,103,008		McKee et al.			
ВС	5	6,136,666		So			
BF	·	6,174,755		Manning			
BC	, 	6,180,486	01/30/01	_eobandung et al.			

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U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. Form PTO 1449 SERIAL NO. PATENT AND TRADEMARK OFFICE (Modified) 211147US99 09/903,784 LIST OF REFERENCES CITED BY APPLICANT APPLICANT AROON TUNGARE ET AL FILING DATE GROUP FEB 1 4 2003 JULY 13, 2001 2826 **U.S. PATENT DOCUMENTS** DOOM ENT **EXAMINER** DATE NAME CLASS SUB FILING DATE INITIAL **CLASS** IF APPROPRIATE CA 3,766,370 10/16/73 Walther CB 4,006,989 02/08/77 Andringa CC 4,284,329 08/18/81 Smith et al. CD 4,777,613 10/11/98 Shahan et al. CE 4,802,182 01/31/89 Thornton et al. CF 4,882,300 11/21/89 Inoue et al. 4,896,194 CG 01/23/90 Suzuki 밁 4,999,842 03/12/91 Huang et al. CĪ 5,081,062 01/14/92 Vasudev et al. 5,155,658 10/13/92 Inam et al. CK 5,248,564 09/28/93 Ramesh CL 5,260,394 11/09/93 Tazaki et al. СМ 5,270,298 12/14/93 Ramesh CN 5,286,985 02/15/94 Taddiken $\overline{\mathsf{co}}$ 5,310,707 05/10/94 Oishi et al. CP 5,326,721 07/05/94 Summerfelt $\overline{c}\overline{\mathbf{Q}}$ 5,404,581 04/04/95 Honjo CR 5,418,389 05/23/95 Watanabe cs 5,436,759 07/25/95 Dijaii et al. 5,576,879 СТ 11/19/96 Nashimoto Cυ 5,606,184 02/25/97 Abrokwah, et al. CV 5,640,267 06/17/97 May et al. 5,674,366 10/07/97 Hayashi et al. CX 5,729,641 03/17/98 Chandonnet et al. 5,790,583 08/04/98 CZ 5,825,799 10/20/98 Ho et al. DĀ 5,857,049 01/05/99 Beranek et al. DΒ 5,674,360 02/23/99 Brunel et al. DC: 5,926,496 07/20/99 Ho et al. DD 5,937,285 08/10/99 Abrokwah, et al. DE 5,981,400 11/09/99 DF 5.990.495 11/23/99 Ohba DG 6,002,375 12/14/99 Corman et al. DH 6,008,762 12/28/99 Nghiem DI 6,055,179 04/25/00 Koganei et al. כם 6,107,653 08/22/00 Fitzgerald DΚ 6,113,690 09/05/00 Yu et al. DL 6,114,996 09/05/00 Nghiem M 6,121,642 09/19/00 Newns DN 6,128,178 10/03/00 Newns DO 6,143,072 11/07/00 McKee et al. DP 6,184,144 02/06/01 Lo ΔQ 6,222,654 04/24/01 Frigo

OF 23 SHEET 3 U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. Form PTO 1449 SERIAL NO. PATENT AND TRADEMARK OFFICE (Modified) 211147US99 09/903,784 APPLICANT SPOEREFERENCES CITED BY APPLICANT AROON TUNGARE ET AL FILING DATE GROUP JULY 13, 2001 2826 FEB 1 4 2003 **U.S. PATENT DOCUMENTS** EXAMINER . DOCUMENT DATE NAME SUB CLASS FILING DATE MAN THE REAL PROPERTY. NUMBER CLASS IF APPROPRIATE ΕA 4,484,332 11/20/84 Hawrylo EΒ 4,815,084 03/21/89 Scifres et al. EC 4,876,219 10/24/89 Eshita et al. FD 4,963,508 10/16/90 Umeno et al. 5,060,031 EΕ 10/22/91 Abrokwah, et al. ΈF 5,063,166 11/05/91 Mooney et al. EG 5,116,461 05/26/92 Lebby et al. 5,127,067 EΗ 06/30/92 Delcoco et al. ΕI 5,144,409 09/01/92 Ма ΕJ 5,293,050 03/08/94 Chapple-Sokol et al EΚ 5,356,831 10/18/94 Calviello et al. ΕL 5,391,515 02/21/95 Kao et al. EM 5,442,191 08/15/95 Ма EΝ 5,444,016 08/22/95 Abrokwah, et al. ΕO 5,480,829 01/02/96 Abrokwah, et al. EP 5,528,414 06/18/96 Oakley EQ 5,614,739 03/25/97 Abrokwah et al. 5,729,394 FR 03/17/98 Sevier et al. ES 5,731,220 03/24/98 Tsu et al. 5,764,676 ΕT 06/09/98 Paoli et al. 07/07/98 Ę 5,777,762 Yamamoto 5,778,018 F۷ 07/07/98 Yoshikawa et al. ΕW 5,778,116 07/07/98 Tomich ΕX 5,801,105 09/01/98 Yano et al. 5,828,080 10/27/98 Yano et al. ΕZ 5,858,814 01/12/99 Goossen et al. FΑ 5,861,966 01/19/99 Ortel FB 5,883,996 03/16/99 Knapp et al. FC 5,995,359 11/30/99 Klee et al. FD 6,058,131 05/02/00 Pan FE 6,137,603 10/24/00 Henmi 6,146,906 11/14/00 lnoue et al. FG 6,173,474 01/16/01 Conrad FΗ 6,180,252 01/30/01 Farrell et al. 4,242,595 12/30/0 Lehovec FJ 4,398,342 08/16/83 Pitt et al. 4,424,589 FΚ 01/03/84 Thomas et al. FL 4,876,208 10/24/89 Gustafson et al. FΜ 4,482,422 11/84 McGinn et al. N 4,667,088 05/19/87 Kramer 4,772,929 FΟ 09/20/88 Manchester et al. FΡ 4,841,775 06/27/89 lkeda et al. FQ 4,845,044 07/04/89 Ariyoshi et al.

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The second		GA	4,868,376	09/19/89	Lessin et al.		OLAGO	II AFFROFRIATE
	,	GB	4,885,376	12/05/89	Verkade	i		
		GC	4,888,202	12/89	Murakami et al.	<u> </u>		
		GD	4,891,091	12/90	Wanlass et al.	 		<u> </u>
		GE	5,051,790	09/24/91	Hammer			
		GF	5,055,445	10/08/91	Belt et al.			-
		GG	5,081,519	11/14/92	Nishimura et al.			
		GH	5,143,854	09/01/92	Pirrung et al.			
		GI	5,185,589	02/09/93	Krishnaswamy et al.			
		GJ	5,191,625	03/02/93	Gustavsson			
		GK	5,194,397	03/16/93	Cook et al.			
		GL	5,208,182	05/04/93	Narayan et al.			
		GM	5,216,729	06/01/93	Berger et al.			
		GN	5,314,547	05/24/94	Heremans et al.			
		GO	5,352,926	10/04/94	Andrews			
		GP	5,356,509	10/18/94	Terranova et al.			-
		GQ	5,371,734	12/06/94	Fischer			
		GR	5,372,992	12/94	Itozaki et al.			
		GS	5,405,802	04/11/95	Yamagata et al.		··	· · · · · · · · · · · · · · · · · · ·
		ЗТ	5,442,561	08/15/95	Yoshizawa et al.			
		3U	5,453,727	09/26/95	Shibasaki et al.			
		3V ∤	5,466,631	11/14/95	Ichikawa et al.			
		SW (5,473,047	12/05/95	Shi			
		SX 8	5,473,171	12/95	Summerfelt			
		3Y (5,479,033	12/26/95	Baca et al.			
	C	SZ E	5,486,406	01/23/96	Shi			
)-	IA E	5,491,461	02/13/96	Partin et al.			
	-	IB 5	5,492,859	02/20/96	Sakaguchi et al.			
	}	IC 5	5,494,711	02/27/96	Takeda et al.			
	-	ID 5	5,504,035	04/02/96	Rostoker et al.			
)-	IE 5	5,504,183	04/02/96	Shi			
	H	IF 5	5,511,238	04/23/96	Bayraktaroglu			
		IG 5	,512,773	04/96	Wolf et al.			
	Н	H 5	,515,047	05/07/96	Yamakido et al.			
	Н	1 5	,515,810	05/14/96	Yamashita et al.			
	Н	J 5	,519,235	05/96	Ramesh			
	Н	K 5	,549,977	08/96	Jin et al.			
	Н	L 5	,551,238	09/03/96	Prueitt			
	Н			09/03/96	Shi	-		
	Н	N 5,	,589,284	12/31/96	Summerfelt et al.			
	Н	0 5,	,602,418	2/11/97	lmai et al.			
	Н	P 5,	633,724	5/27/97	King et al.			

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		.`.		FILING DATE JULY 13, 2001		GROUP	
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XAMINER	1.5	DOCUMENT	DATE	U.S. PATENT DOCUMENTS			
MITIAL 14		NUMBER	DATE	NAME	CLASS	SUB	FILING DATE
Po	IA	5,650,646	07/22/97	Summerfelt		OLAGO	II AFFROFRIA
<u> </u>	IB	5,656,382	08/12/97	Nashimoto			
	IC	5,659,180	08/19/97	Shen et al.			
	ID	5,661,112	08/26/97	Hatta et al.			
<i>T</i>	ΙE	5,679,965	11/95	Schetzina			
	IF	5,725,641	03/10/98	MacLeod			
	IG	5,745,631	04/28/98	Reinker		-	-
· ,,,	IH	5,776,621	07/07/98	Nashimoto		 	-
	11	5,777,350	07/07/98	Nakamura et al.			
	IJ	5,789,845	08/04/98	Wadaka et al.		 	
	iĸ	5,792,569	08/11/98	Sun et al.			
	IL.	5,792,679	08/11/98	Nakato			
	IM	5,796,648	08/18/98	Kawakubo et al.			
	IN	5,801,072	09/01/98	Barber			
	10	5,812,272	09/22/98	King et al.			
	IP	5,814,583	09/98	Itozaki et al.			
1	IQ	5,825,055	10/20/98	Summerfelt			
+	iR	5,827,755	10/27/98	Yonchara et al.			
	is	5,833,603	11/10/98	Kovacs et al.			
	IT	5,838,035	11/17/98	Ramesh			
	U	5.844.260	12/01/98	Ohori			
-	-	5,846,846	12/08/98				
	w	5,863,326	01/26/99	Suh et al.			
-	 _	5,872,493		Nause et al.			
		5,879,956	02/16/99	Ella			
	Y Z		03/99	Seon et al.			
		5,880,452		Plesko			
-		5,883,564	03/16/99	Partin			
\bot		5,907,792		Droopad et al.			***
-		5,937,274		Kondow et al.			
+		5,948,161		Kizuki			
		5,959,879		Koo			-
		5,966,323		Chen et al.			
		5,987,011		Toh			
l hi		6,022,140		Fraden et al.			
l hi	1	6,022,410	02/08/00	Yu et al.			
μ.		6,023,082	02/08/00	McKee et al.			
J٢	< 0	6,028,853	02/22/00	Haartsen			
JL		5,049,702	04/11/00	ham et al.			
hν	1 6	5,078,717	06/20/00	Nashimoto et al	- -		
Jun Jun	1 6	5,088,216	07/00 L	aibowitz et al.			
7 hc) 6	5,090,659		aibowitz et al.	+		
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Form PTO 1449 U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. SERIAL NO. (Modified) PATENT AND TRADEMARK OFFICE 211147US99 09/903,784 APPLICANT LIST OF REFERENCES CITED BY APPLICANT AROON TUNGARE ET AL FILING DATE GROUP JULY 13, 2001 2826 JFBB 1 4 2003 U.S. PATENT DOCUMENTS EXAMINER. DOCUMENT DATE CLASS NAME SUB FILING DATE INITIAL NUMBER **CLASS** IF APPROPRIATE Co The Co 6,153,454 11/28/00 Krivokapic ΚB 6,191,011 02/01 Gilboa et al кc 6,204,737 03/20/01 ΚĎ 6,224,669 05/01/01 Yi et al. ΚE 6,225,051 05/01/01 Sugiyama et al. KF 6,241,821 06/05/01 Yu et al. KG 6,265,749 07/24/01 Gardner et al. 6,313,486 KН 11/01 Kencke et al. ΚI 6,316,832 11/13/01 Tsuzuki et al. 2002/0008234 01/02 Emrick ΚK 3,670,213 06/13/72 Nakawaga et al. KL 4,756,007 07/05/88 Qureshi et al. КМ 4,773,063 09/20/88 Hunsperger et al. KN 5,394,489 02/28/95 Koch 5,406,202 KO 04/11/95 Mehrgardt et al. KP 5,528,067 06/18/96 Farb et al. KQ 5,572,052 11/05/96 Kashihara et al. KR 5,767,543 06/16/98 Doms et al. ĸs 6,175,497 01/16/01 Tseng et al. KT 6,197,503 03/06/01 Vo-Dinh et al. ΚŪ 6,248,459 06/19/01 Wang et al. ΚV 6,252,261 06/26/01 Usui et al. ΚW 6,255,198 07/03/01 Linthicum et al. 6,268,269 07/31/01 Lee et al. KY 6,291,319 09/18/01 Yu et al. ΚZ 6,316,785 11/13/01 Nunoue et al. _A 6,343,171 01/29/02 Yoshimura et al. B 4,965,649 10/23/90 Zanio et al. <u>.c</u> 6,253,649 05/01 Kawahara et al. .D 6,211,096 04/01 Allman et al. LE 6,239,449 05/29/01 Fafard et al. h F 2001/0013313 08/16/01 Droopad et al. LG 6,184,044 02/06/01 Sone et al. LH 6,011,646 01/04/00 Mirkarimi et al. 5,227,196 LI 07/13/93 ltoh LJ 6,150,239 11/21/00 Goesele et al. LK 5,441,577 08/15/95 Sasaki et al. LL 4,459,325 07/10/84 Nozawa et al. LM 07/12/83 4,392,297 Little Z 4,289,920 09/15/81 Hovel LO 5,281,834 01/25/94 Cambou et al. ΙĐ 4,901,133 02/13/90 Curran et al. ū 5,514,904 05/07/96 Onga et al.

ATTY DOCKET NO. SERIAL NO. Form PTO 1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE 211147US99 09/903,784 **APPLICANT** LISTOR FERENCES CITED BY APPLICANT **AROON TUNGARE ET AL** FILING DATE **GROUP** FEB 1 4 2003 JULY 13, 2001 2826 **U.S. PATENT DOCUMENTS** EXAMINER INITIAL DOCUMENT SUB **FILING DATE** DATE **CLASS** NAME NUMBER **CLASS** IF APPROPRIATE FF. MA 5,553,089 09/03/96 Seki et al. MB 5,528,057 06/18/96 Yanagase et al. MC 6,229,159 05/08/01 Suzuki MD 4,748,485 05/31/88 Vasudev ME 4.984,043 01/08/91 Vinal MF 5,754,319 05/19/98 Van De Voorde et al. MG 6,108,125 08/22/00 Yano МН 5.073.981 12/17/91 Giles et al. MI 5,140,651 08/18/92 Soref et al. MJ 5,610,744 03/11/97 Ho et al. MK 6,362,017 03/26/02 Manabe et al. ML 6,242,686 06/05/01 Kishimoţo et al. MM 5,689,123 11/18/97 Major et al. MN 5,670,800 09/23/97 Nakao et al. MO 5,067,809 11/26/91 Tsubota 5,596,205 MP 01/21/97 Reedy et al. MQ 6,175,555 01/16/01 Hoole MR 5,357,122 10/18/94 Okubora et al. MS 4,084,130 04/11/78 Holton MT 6,093,302 07/25/00 Montgomery MU 6,372,813 04/16/02 Johnson et al. MV 5,608,046 03/04/97 Cook et al. MW 5,955,591 09/21/99 Imbach et al. MX 6,022,963 02/08/00 McGall et al. MY 6,083,697 07/04/00 Beecher et al. ΜZ 5,063,081 11/05/91 Cozzette et al. NA 5,479,317 12/26/95 Ramesh 5,306,649 NB 04/26/94 Hebert NC 5,962,069 10/05/99 Schindler et al. ND 5,541,422 07/30/96 Wolf et al. 5,873,977 NE 02/23/99 Desu et al. NF 5,538,941 07/23/96 Findikoglu et al. NG 6,046,464 04/04/00 Schetzina NH 6,235,145 05/22/01 Li et al. 5,610,744 03/11/97 NI Ho et al. NJ 5,280,013 01/18/94 Newman et al. NK 6,348,373 B1 02/19/02 Ma et al. 6,339,664 B1 NL 01/15/02 Farjady et al. NM 4,439,014 03/27/84 Stacy et al. NN 4,889,402 12/26/89 Reinhart NO 5,963,291 10/05/99 Wu et al. NP 6,011,641 01/04/00 Shin et al. NQ 6,340,788 B1 01/22/02 King et al.

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				U.S. PATENT DOCUMENTS				
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
FE	OA	5,807,440	09/15/98	Kubota et al.				
	ОВ	4,681,982	07/21/87	Yoshida				
	ос	4,629,821	12/16/86	Bronstein-Bonte et al.				
	OD	4,452,720	06/05/84	Harada et al.				
	OE	3,935,031	01/27/76	Adler				
	OF	5,760,426	06/02/98	Marx et al.				
	OG	5,053,835	10/01/91	Horikawa et al.				
	ОН	6,326,645 B1	12/04/01	Kadota				
	OI	5,770,887	06/23/98	Tadatomo et al.				
	Ol	6,372,356 B1	04/16/02	Thornton et al.				
	ок	4,774,205	09/27/88	Choi et al.				
	OL	6,359,330 B1	03/19/02	Goudard				
	ОМ	5,312,765	05/17/94	Kanber				
	ON	5,734,672	03/31/98	McMinn et al.		Ĭ		
	00	6,367,699 B2	04/09/02	Ackley				
	OP	5,530,235	06/25/96	Stefik et al.			· ·	
	OQ.	5,623,552	04/22/97	Lane				
	OR	5,481,102	01/02/96	Hazelrigg, Jr.				
	os	6,134,114	10/17/00	Ungermann et al.				
	ОТ	5,984,190	11/16/99	Nevill				
	ΟU	5,789,733	08/04/98	Jachimowicz et al.				
	ov	5,753,300	05/19/98	Wessels et al.				
	ow	6,208,453	03/27/01	Wessels et al.				
	ОХ	5,886,867	03/23/99	Chivukula et al.				
	OY	5,028,976	07/02/91	Ozaki et al.				
	oz	5,869,845	02/09/99	Vander Wagt et al.				
	PA	5,596,214	01/21/97	Endo				
_	РВ	6,391,674 B2	05/21/02	Ziegler				
		6,275,122 B1	08/14/01	Speidell et al.				
		6,238,946 B1	05/29/01	Ziegler				
		6,210,988 B1	04/03/01	Howe et al.				
/_		6,392,257	05/21/02	Ramdani et al.				
	$\overline{}$	4,442,590	04/17/84	Stockton et al.			·	
		5,603,764	02/18/97	Matsuda et al.				
	-+	6,087,681	06/11/00	Shakuda				
		5,132,648	07/21/92	Trinh et al.				
		6,427,066	07/30/02	Grub				
		2002/0072245	06/13/02	Ooms et al.				
		6,278,138 B1	08/21/01	Suzuki				
	-+	5,888,296	03/30/99	Ooms et al.				
		5,198,269	03/3093	Swartz et al.				
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	PQ	2002/0047143	04/25/02	Ramdani et al.				

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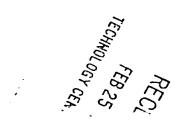
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